## TJK/190/L.W.

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

		In re application of Byoung-Youp KIM et al.  No. 2000-46691  Korean Filing Date: August 11, 2000  METHOD OF FORMING A MOCVD-T THIN FILM  On the property of th	IN
		PRELIMINARY AMENDMENT	
		Assistant Commissioner for Patents Washington, D.C. 20231	
		Dear Sir:  Please amend the subject application as follows:  In the Specification	
,		-CROSS REFERENCE TO RELATED APPLICATION	
1		This application claims the priority of Korean patent application Serial No. 2000-46691	ŀ
	sec ast	filed on August 11, 2000.	
		Respectfully submitted,  Date: S.	